

WEST Search History

DATE: Sunday, November 10, 2002

Set Name Query

side by side

Hit Count Set Name

result set

DB=USPT,PGPB,JPAB,EPAB,DWPI,TDBD; PLUR=YES; OP=ADJ

L10 (ALE or ALD or (atomic layer near2 (deposit\$3 or epitax\$5))) and (cold wall) 38 L10

L9 (ALE or ALD or (atomic layer near2 (deposit\$3 or epitax\$5))) and (hot wall) 29 L9

DB=USPT; PLUR=YES; OP=ADJ

L8 4570328.pn. 1 L8

DB=JPAB,EPAB,DWPI,TDBD; PLUR=YES; OP=ADJ

L7 (\$3CVD or (vapor deposit\$3) or ALE or ALD or (atomic layer near2 (deposit\$3 or epitax\$5))) and ((chamber or reactor or wall or vessell or vessel) near4 (temperature) near4 (higher or hotter) near4 (substrate or wafer or sample or pedestal or support or chuck or susceptor)) 8 L7

DB=USPT,PGPB; PLUR=YES; OP=ADJ

L6 (\$3CVD or (vapor deposit\$3) or ALE or ALD or (atomic layer near2 (deposit\$3 or epitax\$5))) and ((chamber or reactor or wall or vessell or vessel) near4 (temperature) near4 (higher or hotter) near4 (substrate or wafer or sample or pedestal or support or chuck or susceptor)) 104 L6

L5 (\$3CVD or (vapor deposit\$3) or ALE or ALD or (atomic layer near2 (deposit\$3 or epitax\$5))) and ((chamber or reactor or wall or vessell or vessel) near8 (temperature) near8 (higher or lower or hotter or colder or different) near8 (substrate or wafer or sample or pedestal or support or chuck or susceptor)) and ((control\$5 or regulat\$5) near4 temperature near4 (chamber or reactor or wall or vessell or vessel)) and ((control\$5 or regulat\$5) near4 temperature near4 (substrate or wafer or sample or pedestal or support or chuck or susceptor)) 112 L5

DB=JPAB,EPAB,DWPI,TDBD; PLUR=YES; OP=ADJ

L4 (\$3CVD or (vapor deposit\$3) or ALE or ALD or (atomic layer near2 (deposit\$3 or epitax\$5))) and ((chamber or reactor or wall or vessell or vessel) near8 (temperature) near8 (higher or lower or hotter or colder or different) near8 (substrate or wafer or sample or pedestal or support or chuck or susceptor)) 61 L4

DB=USPT,PGPB; PLUR=YES; OP=ADJ

L3 L2 and (\$3CVD or (vapor deposit\$3) or ALE or ALD or (atomic layer near2 (deposit\$3 or epitax\$5))) and ((chamber or reactor or wall or vessell or vessel) near8 (temperature) near8 (higher or lower or hotter or colder or different) near8 (substrate or wafer or sample or pedestal or support or chuck or susceptor)) 170 L3
((427/248.1).icls. or (427/255.23).icls. or (427/255.28).icls. or

L2	(427/255.7).icls. or (427/587).icls. or (118/715).icls. or (118/719).icls. or (118/724).icls. or (118/725).icls. or (118/728).icls. or (117/84).icls. or (117/88).icls. or ((117/105)!.ICLS.))	5862	L2
L1	a	6765631	L1

END OF SEARCH HISTORY